

Hiroshi Yoshida

List of Publications by Year in descending order

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1013
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#	ARTICLE	IF	CITATIONS
1	Chemical Patterns for Directed Self-Assembly of Lamellae-Forming Block Copolymers with Density Multiplication of Features. <i>Macromolecules</i> , 2013, 46, 1415-1424.	2.2	201
2	Directed Self-Assembly of Diblock Copolymer Thin Films on Chemically-Patterned Substrates for Defect-Free Nano-Patterning. <i>Macromolecules</i> , 2008, 41, 9267-9276.	2.2	106
3	Reentrant Solid-Liquid Transition in Ionic Colloidal Dispersions by Varying Particle Charge Density. <i>Physical Review Letters</i> , 1998, 80, 5806-5809.	2.9	103
4	Directed Self-Assembly of POSS Containing Block Copolymer on Lithographically Defined Chemical Template with Morphology Control by Solvent Vapor. <i>Macromolecules</i> , 2012, 45, 292-304.	2.2	91
5	Void structure and vapor-liquid condensation in dilute deionized colloidal dispersions. <i>Journal of Chemical Physics</i> , 1995, 103, 10146-10151.	1.2	73
6	Transitions between Ordered and Disordered Phases and Their Coexistence in Dilute Ionic Colloidal Dispersions. <i>Langmuir</i> , 1999, 15, 2684-2702.	1.6	71
7	Topcoat Approaches for Directed Self-Assembly of Strongly Segregating Block Copolymer Thin Films. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2013, 26, 55-58.	0.1	52
8	Nine-fold density multiplication of hcp lattice pattern by directed self-assembly of block copolymer. <i>Polymer</i> , 2009, 50, 4250-4256.	1.8	45
9	Paradoxes of the Repulsion-Only Assumption. <i>Accounts of Chemical Research</i> , 1996, 29, 3-5.	7.6	42
10	Analysis on Deterioration Mechanism of Release Layer in Nanoimprint Process. <i>Journal of Photopolymer Science and Technology</i> = [Fotoporima Konwakai Shi], 2007, 20, 545-548.	0.1	42
11	Control of the Microdomain Orientation in Block Copolymer Thin Films with Homopolymers for Lithographic Application. <i>Langmuir</i> , 2007, 23, 6404-6410.	1.6	41
12	Nonbulk Complex Structures in Thin Films of Symmetric Block Copolymers on Chemically Nanopatterned Surfaces. <i>Macromolecules</i> , 2012, 45, 3986-3992.	2.2	40
13	Localized ordered structure in polymer latex suspensions as studied by a confocal laser scanning microscope. <i>Physical Review B</i> , 1991, 44, 435-438.	1.1	34
14	Morphology of Lamellae-Forming Block Copolymer Films between Two Orthogonal Chemically Nanopatterned Striped Surfaces. <i>Physical Review Letters</i> , 2012, 108, 065502.	2.9	34
15	Directed Assembly of Block Copolymers in Thin to Thick Films. <i>Macromolecules</i> , 2013, 46, 3915-3921.	2.2	34
16	Inhomogeneity of solute distribution in ionic systems. <i>Faraday Discussions of the Chemical Society</i> , 1990, 90, 153.	2.2	31
17	Ordering of latex particles and ionic polymers in solutions. <i>Langmuir</i> , 1990, 6, 296-302.	1.6	31
18	Novel Crystallization Process in Dilute Ionic Colloids. <i>Langmuir</i> , 1998, 14, 569-574.	1.6	29

#	ARTICLE	IF	CITATIONS
19	Glass-modified stress waves for adhesion measurement of ultra thin films for device applications. Journal of the Mechanics and Physics of Solids, 2003, 51, 1395-1412.	2.3	26
20	Colloidal crystal growth. Journal of the Chemical Society, Faraday Transactions, 1991, 87, 371.	1.7	24
21	ESR Study of Irradiated Pyridine. Journal of Chemical Physics, 1966, 45, 2894-2897.	1.2	23
22	Directed Self-Assembly of Cage Silsesquioxane Containing Block Copolymers via Graphoepitaxy Techniques. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2010, 23, 155-159.	0.1	23
23	Reentrant Order~Disorder Transition in Ionic Colloidal Dispersions by Varying Particle Charge Density. Langmuir, 1999, 15, 4198-4202.	1.6	22
24	Observation of Fine Structure in Bicontinuous Phase-Separated Domains of a Polymer Blend by Laser Scanning Confocal Microscopy. Macromolecules, 2001, 34, 5186-5191.	2.2	22
25	Formation of long-range stripe patterns with sub-100nm half-pitch from directed self-assembly of block copolymer. Journal of Polymer Science, Part B: Polymer Physics, 2010, 48, 2297-2301.	2.4	22
26	ESR Spectra of Trapped Electrons in β -irradiated 3-Methylpentane. Journal of Chemical Physics, 1967, 46, 810-811.	1.2	21
27	Ordering Cylindrical Microdomains for Binary Blends of Block Copolymers with Graphoepitaxy. Macromolecular Rapid Communications, 2007, 28, 2137-2144.	2.0	20
28	Effect of oxygen addition to an argon plasma on etching selectivity of poly(methyl methacrylate) to polystyrene. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2013, 12, 041309.	1.0	20
29	Two-dimensional Fourier analysis and quasielastic light-scattering measurements of colloid crystals. Physical Review B, 1988, 38, 10852-10859.	1.1	18
30	Microscopic observation and quasielastic light-scattering measurements of colloid crystals. Determination of the radial distribution function and structure factor for the two-state structure. Journal of the American Chemical Society, 1990, 112, 592-596.	6.6	16
31	Directed Self-assembly with Density Multiplication of Cage Silsesquioxane-containing Block Copolymer via Controlled Solvent Annealing. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2011, 24, 577-580.	0.1	15
32	Study of the Internal Structure of Latex Dispersions by Laser Scanning Microscope. Confirmation of Void Structure. Chemistry Letters, 1992, 21, 2081-2084.	0.7	14
33	Cross-sectional Imaging of Block Copolymer Thin Films on Chemically Patterned Surfaces. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2010, 23, 149-154.	0.1	14
34	Slowing the translocation of single-stranded DNA by using nano-cylindrical passage self-assembled by amphiphilic block copolymers. Nanoscale, 2016, 8, 18270-18276.	2.8	13
35	Density Multiplication by Directed Self-assembly of Block Copolymer Binary Blends. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2009, 22, 229-233.	0.1	11
36	Electron spin resonance study of radiation-induced solid-state polymerization of conjugated dienes. Journal of Polymer Science Part A-1, Polymer Chemistry, 1966, 4, 2710-2713.	0.7	10

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37	Restricted Motion of a Particle Trapped inside a Void in a Colloidal Dispersion. <i>Langmuir</i> , 1995, 11, 2853-2855.	1.6	10
38	ESR Study on Irradiated Pyridine: Effect of Iodine Addition. <i>Journal of Chemical Physics</i> , 1967, 46, 2808-2810.	1.2	7
39	Life span of a local structure in colloidal suspensions. <i>Journal of the American Chemical Society</i> , 1989, 111, 2347-2348.	6.6	7
40	Advanced CD-SEM metrology for pattern roughness and local placement of lamellar DSA. <i>Proceedings of SPIE</i> , 2014, , .	0.8	7
41	Growth of local structure in colloidal suspensions. <i>Physical Review B</i> , 1990, 41, 5403-5406.	1.1	6
42	Selective and Anisotropic Copper Electroplating Using Copper Overburden with an Inhibiting Additive. <i>Electrochemical and Solid-State Letters</i> , 2010, 13, D23.	2.2	6
43	Design of Thermoresponsive Polymers Toward Antibody Purification. <i>ACS Applied Polymer Materials</i> , 2019, 1, 1925-1929.	2.0	6
44	Inhomogeneous distribution of charged colloidal particles studied by confocal laser scanning microscopy. <i>Colloids and Surfaces A: Physicochemical and Engineering Aspects</i> , 2000, 174, 55-77.	2.3	3
45	Improved lithography by directed self-assembly of ultra-high-density patterns. <i>SPIE Newsroom</i> , 0, , .	0.1	3
46	Tailoring Microdomain Orientation in Block Copolymer Thin Films for Lithographic Application. <i>Materials Research Society Symposia Proceedings</i> , 2006, 961, 1.	0.1	2
47	Advanced trench filling process by selective copper electrodeposition for ultra fine printed wiring board fabrication. , 2010, , .		2
48	Reducing hole-size variation and defect ratio after pattern transfer by using self-assembled polymer with spherical structure. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2013, 31, 041807.	0.6	2
49	Effect of Free Radicals on the Proton Resonance of Irradiated Polymers. <i>Journal of the Physical Society of Japan</i> , 1962, 17, 581-581.	0.7	1
50	Line edge roughness measurement technique for fingerprint pattern in block copolymer thin film. , 2013, , .		1
51	Analyses of Morphologies in Block Copolymer Thin Films by Grazing Incidence Small Angle X-ray Scattering. <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2014, 27, 751-755.	0.1	1
52	P-23: Thin Durable Metal Substrates for High-Resolution a-Si TFT Active Matrix Displays. <i>Digest of Technical Papers SID International Symposium</i> , 2006, 37, 266.	0.1	0
53	Alignment of Cylindrical Microdomains on a Grating Substrate by Binary Blends of Polystyrene-Poly(methyl methacrylate). <i>Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi]</i> , 2007, 20, 505-510.	0.1	0
54	Silicon Mold Etching with Hard Mask Stack Using Spherical Structure of Block Copolymer for Bit-Patterned Media with 2.8 Tbit/in. ² . <i>Japanese Journal of Applied Physics</i> , 2013, 52, 086201.	0.8	0

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55	Corrosion Resistance of Next Generation Magnetic Disk (2). Zairyo To Kankyo/ Corrosion Engineering, 2013, 62, 52-55.	0.0	0
56	Creation of Different Types of Patterns in the Selective“Area of Thin Films for Block Copolymer Containing Silsesquioxanes. Science of Advanced Materials, 2015, 7, 969-973.	0.1	0